

*CLAIM AMENDMENTS*

Claims 1-13 (Canceled).

14. (Currently Amended) A substrate treatment ~~assembly~~ apparatus comprising:  
a substrate heating device for maintaining a substrate at a temperature higher than room temperature;  
a wetting device for ~~obtaining~~ producing a wet ozone-containing gas by wetting an ozone-containing gas with a treatment solution;  
a supply device for supplying ~~said the~~ wet ozone-containing gas from the wetting device to a work object on a surface of ~~said the~~ substrate, said supply device comprising a gas disperser including a plurality of apertures aligned in a plurality of rows in a width direction of the work object, the apertures in adjacent rows not being aligned with each other in a direction perpendicular to the rows, and at least one of said gas disperser and the substrate being movable in a direction perpendicular to the rows;  
a gas conduit connecting said wetting device to said supply device; and  
a wet ozone-containing gas heating device for heating ~~said the~~ wet ozone-containing gas ~~so as to be at a temperature approximately at least equal to or greater than the temperature of said the~~ substrate.

Claim 15 (Canceled).

16. (Currently Amended) The substrate treatment assembly according to Claim 15 wherein spacing between adjacent rows of ~~aperture~~ apertures in said gas disperser is at least 5 mm ~~or more~~.

17. (Currently Amended) A substrate treatment ~~assembly~~ apparatus for supplying an ozone-containing gas and a treatment solution to a work object on a surface of a substrate ~~through, the assembly including a treatment agent supply plate disposed facing said the work object and through which the treatment solution is supplied, in which spacing between wherein a surface of said the work object and is spaced from said treatment agent supply plate is by a distance in a range between 0.1 mm and 1.0 mm.~~